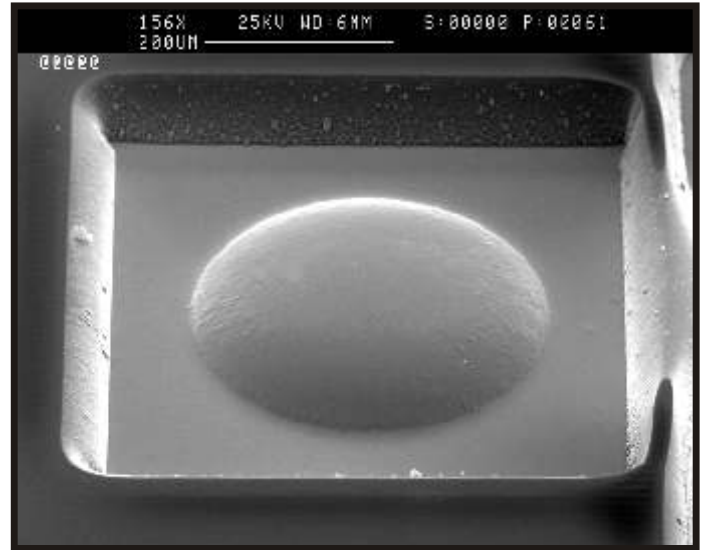
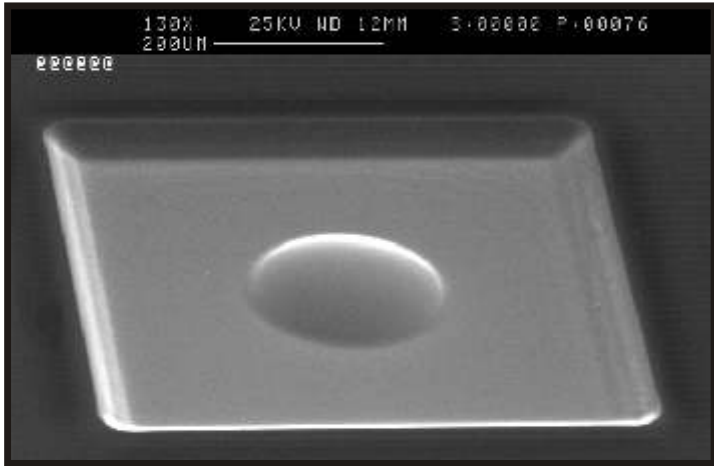


Plasmalab Data

GaP Lens - Etching by ICP

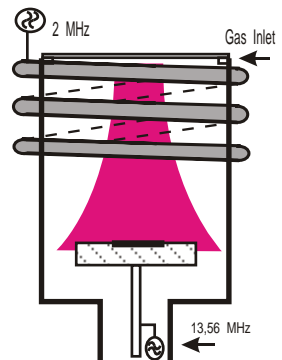


OPT application lab:
transfer of a PR lens into GaP
by ICP - RIE

Plasmalab 80 Plus

Plasmalab System 133

Plasmalab System 100



Technology:

Reactive Ion Etching
with ICP Source (2 or 13 MHz)
Inductive Coupled Plasma
RF driven substrate electrode

Results:

Rate : $\geq 1 \mu\text{m}/\text{min}$
good uniformity
controllable selectivity to PR
smooth surface